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Model study of penetration of ions from solution into organic self-assembled-monolayer on metal substrate

Anton Kokalj

Department of Physical and Organic Chemistry

in cooperation with: D. Costa Chemie ParisTech

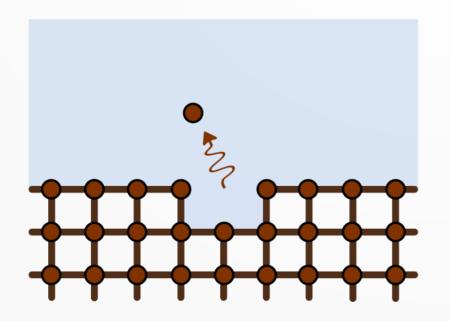


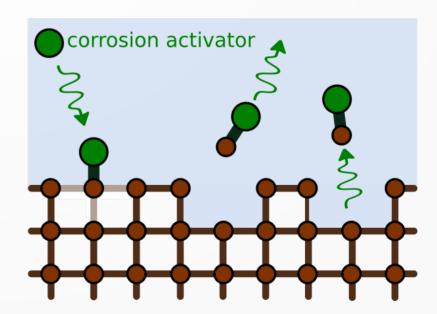
Jožef Stefan Institute, Ljubljana, Slovenia

Introducing the context



Corrosion of metals: $M \rightarrow M^{z+} + ze^{-}$



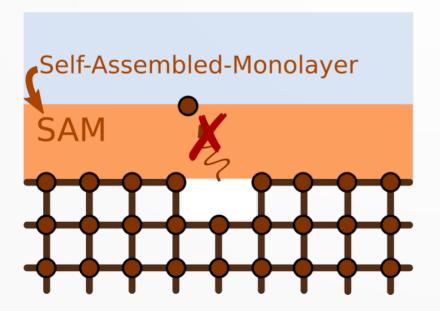


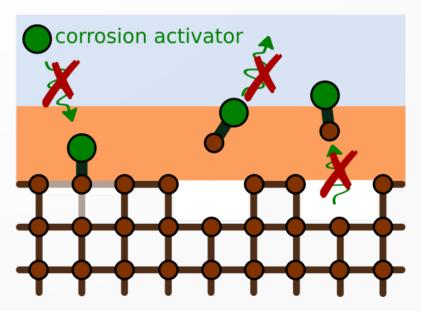
Introducing the context



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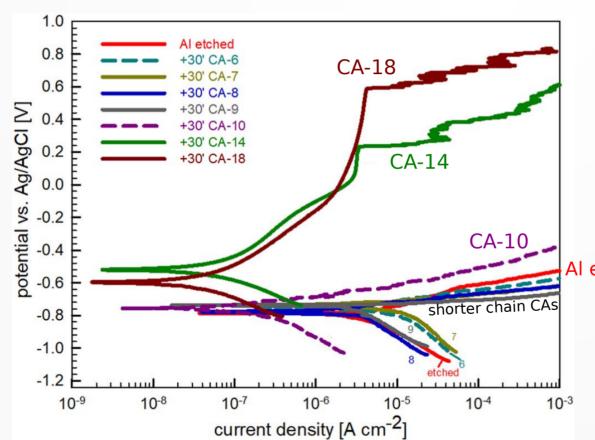
corrosion can be reduced with surfactant inhibitors that form a self-assembled-monolayer (SAM) on the surface of a metal





Carboxylic acids (CA) as inhibitors of Al





$$CA-n = C_nH_{2n}O_2$$

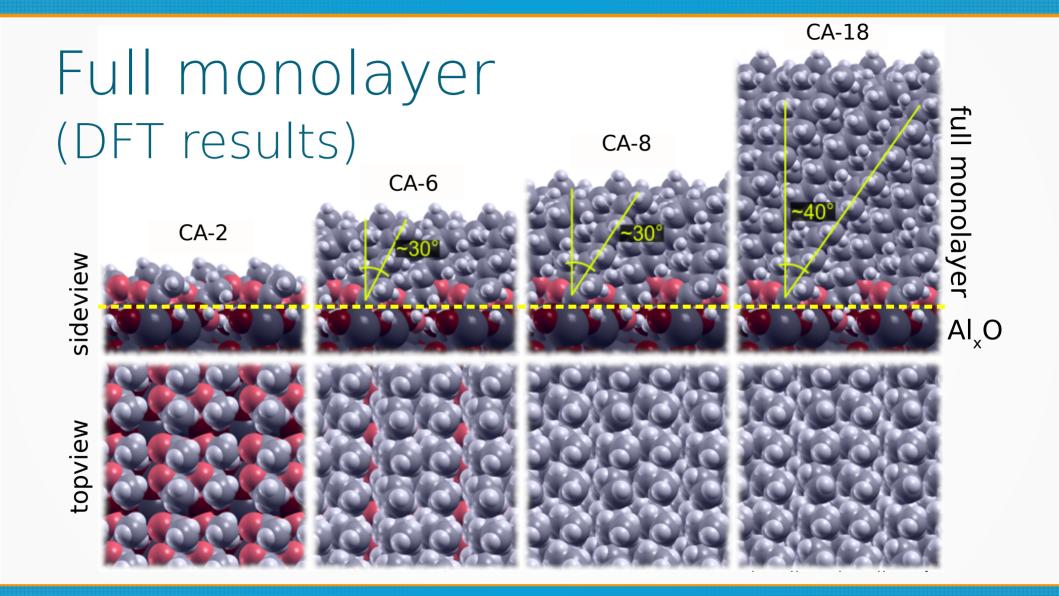
(CA-8 = octanoic acid)

only long-chain CAs are efficient inhibitors

Al etched



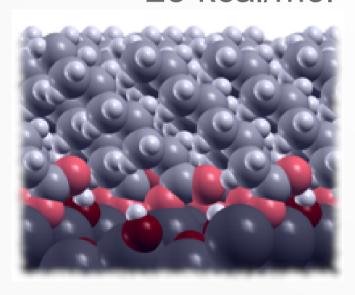
Milošev et al., J. Electrochem. Soc. 166, C3131

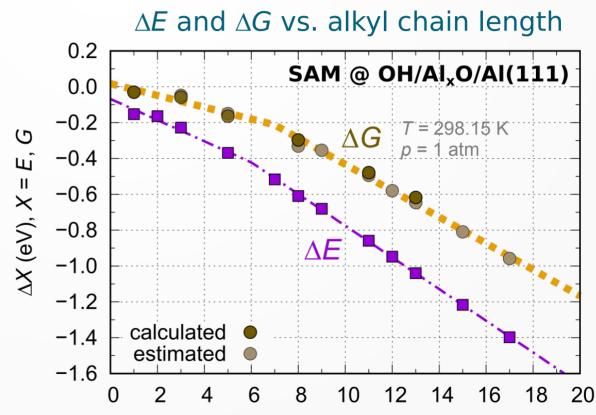


Adsorption energy at full monolayer



1 eV ≈ 100 kJ/mol ≈ 25 kcal/mol

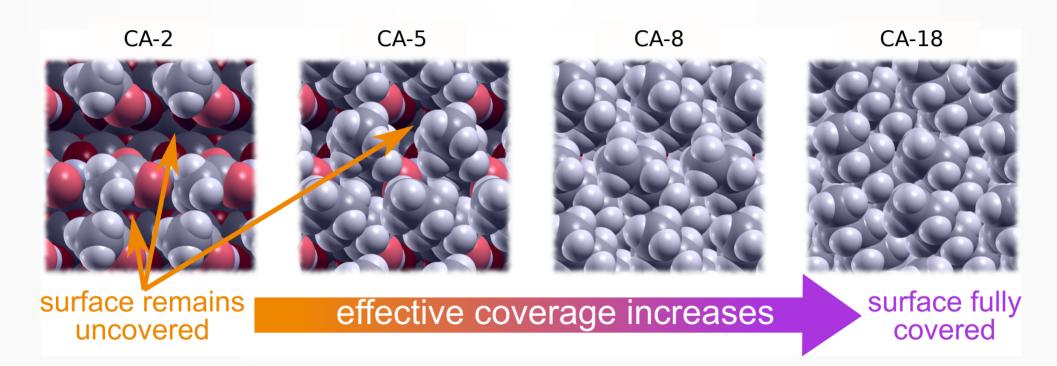




Alkyl chain length, n

Effective coverage

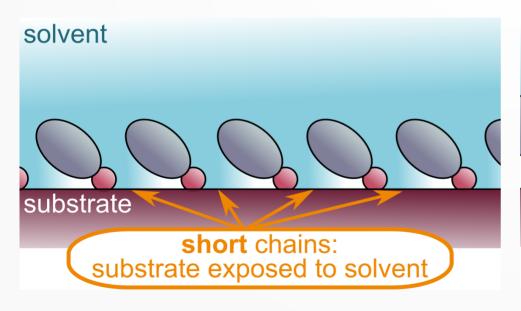


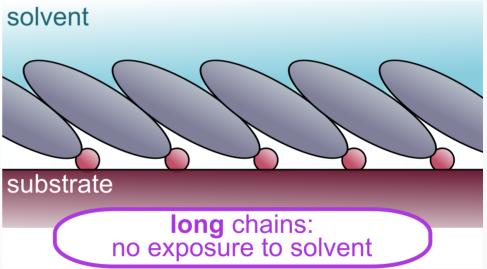


longer alkyl chain = smaller gaps = greater effective coverage

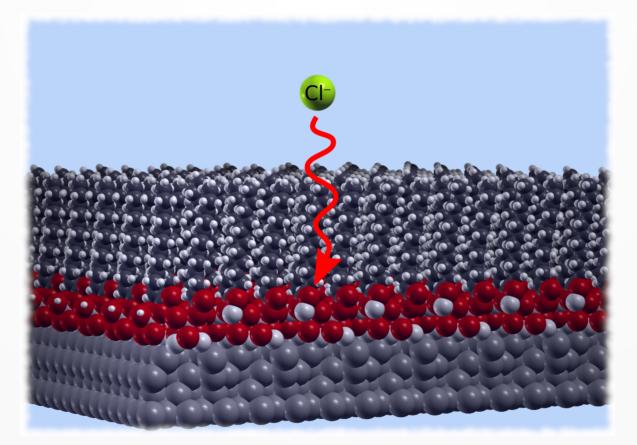
Effective coverage





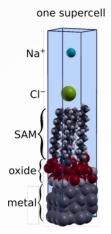


Penetration of Cl-through SAM ••••



Kokalj & Costa, J. Electrochem. Soc. 168, 071508

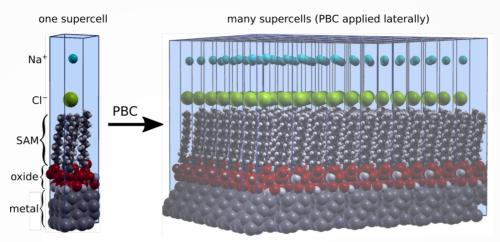
Beware of PBC (periodic boundary conditions)!



PBC & divergent Coulomb interactions:

add Na+ to make supercell neutral

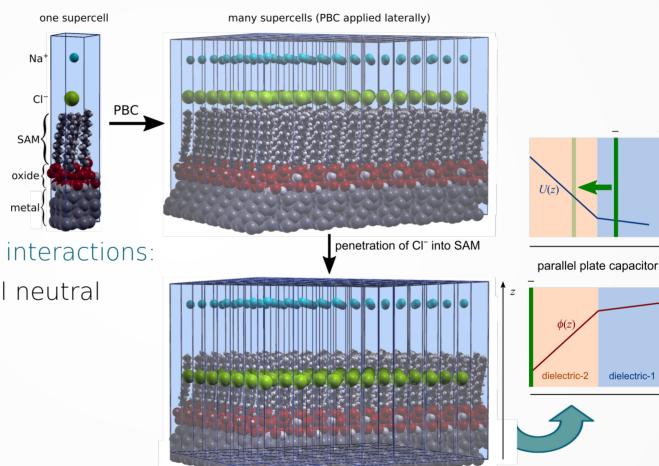
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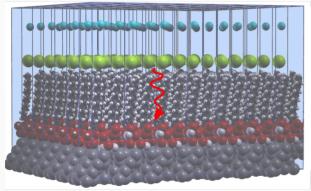
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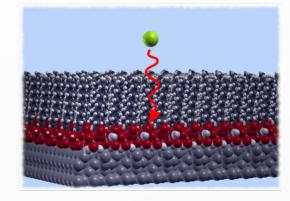
Beware of PBC





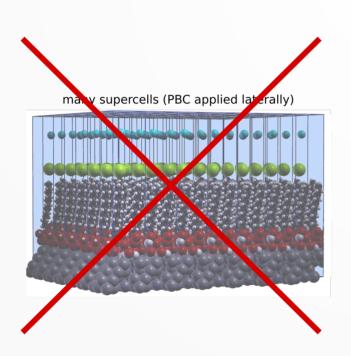




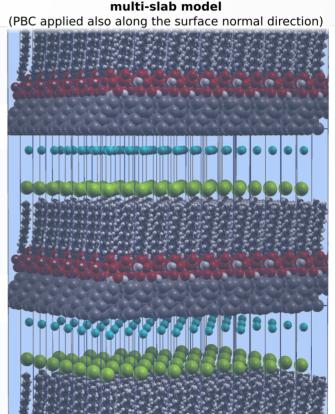


3D PBC: beware of artifacts





multi-slab model

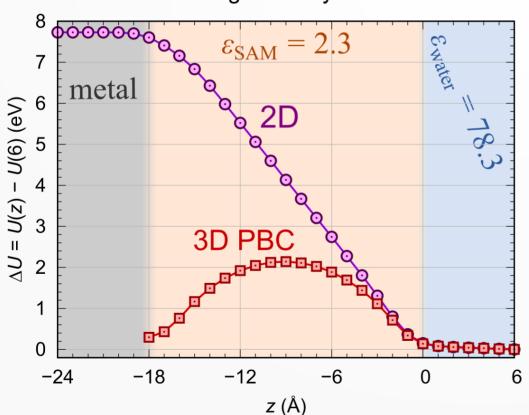


used by plane-wave DFT codes

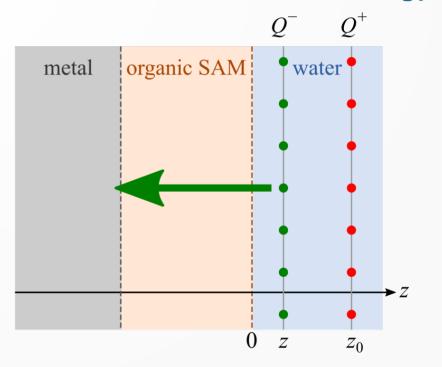
3D PBC: beware of artifacts







inter-ion electrostatic energy

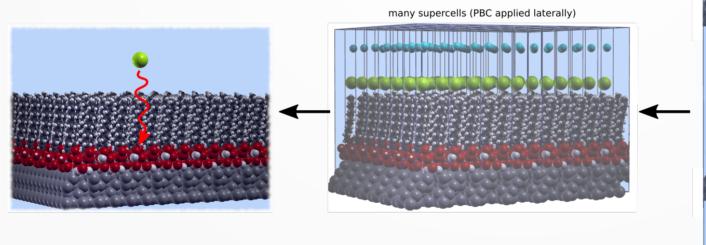


SAM = self assembled monolayer

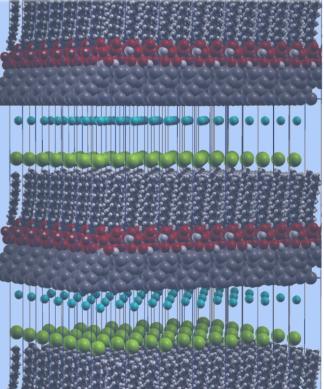
3D PBC: beware of artifacts



reverse engineer to get rid of PBC artifacts

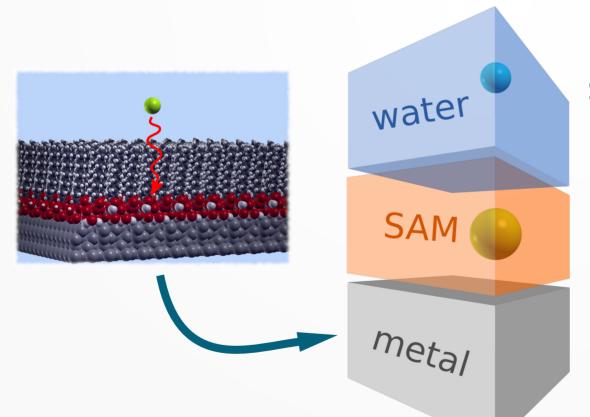


multi-slab model
(PBC applied also along the surface normal direction)



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Penetration of Cl-through SAM ••••



Simplified model calculations:

- metal/SAM/water described by implicit continuum slabs
- ions treated explicitly (ionic solvation considered)
- elastic penalty for Clpenetration into SAM neglected

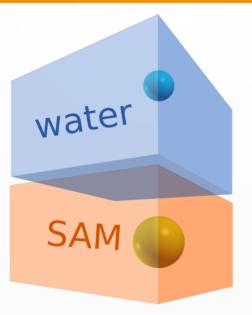
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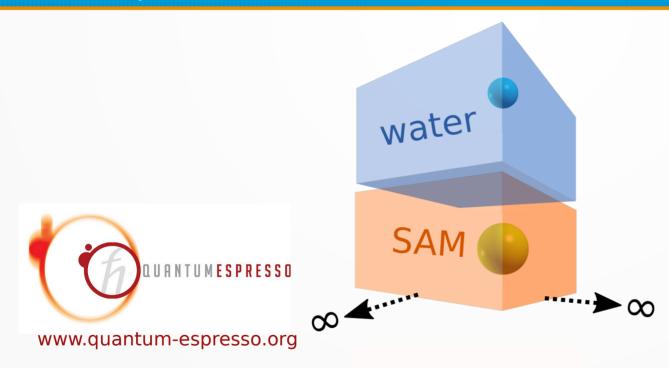




Simplified model calculations:

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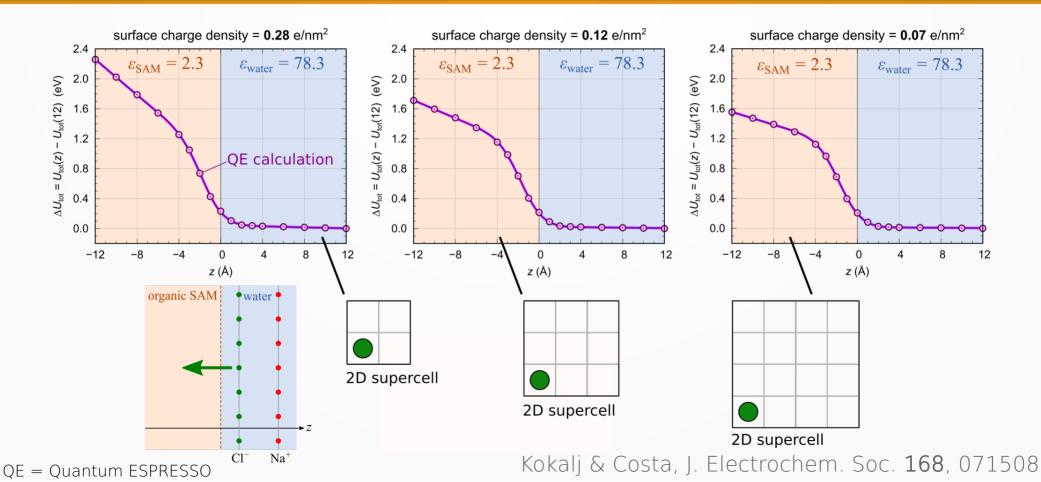


Environ plugin of Quantum ESPRESSO (QE) www.quantum-environ.org

SAM = self assembled monolayer

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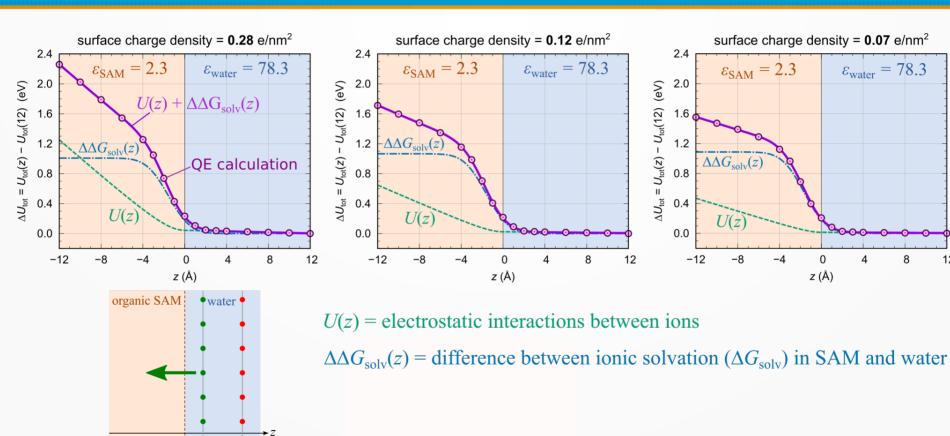






12

 $\varepsilon_{\rm water} = 78.3$



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Na

How to understand $\Delta\Delta G_{ m solv}$



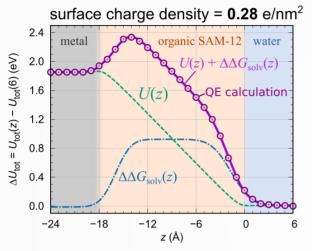
Born solvation model:

$$\Delta G_{
m solv}^{
m Born} = -rac{q_{
m ion}^2}{2r_{
m ion}} \left(1 - rac{1}{arepsilon}
ight)$$
 [in Hartree atomic units]

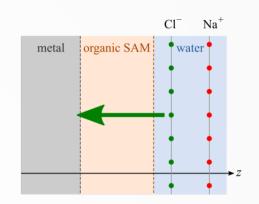
SAM vs. water difference:

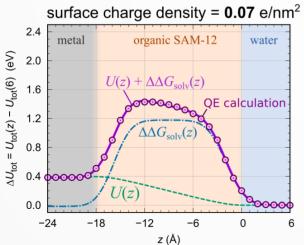
$$\Delta \Delta G_{\text{solv}}^{\text{Born}} = \Delta G_{\text{solv}}^{\text{Born}}(\text{SAM}) - \Delta G_{\text{solv}}^{\text{Born}}(\text{water}) = \frac{q_{\text{ion}}^2}{2r_{\text{ion}}} \left(\frac{1}{\varepsilon_{\text{SAM}}} - \frac{1}{\varepsilon_{\text{water}}}\right)$$

Full system: metal/SAM/water



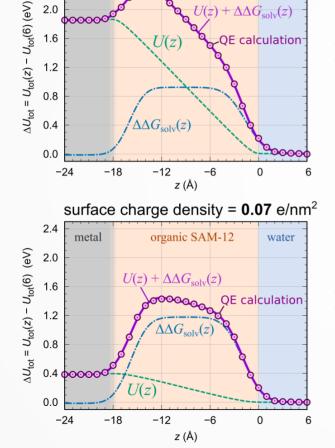
QE = Quantum ESPRESSO





SAM-12 = SAM composed of CA-12 (CA = carboxylic acid)

Full system: metal/SAM/water

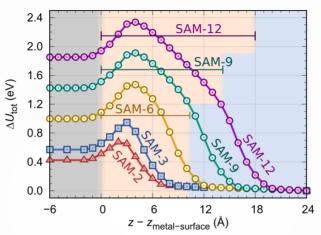


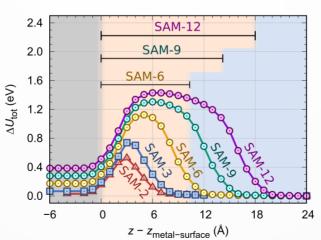
surface charge density = **0.28** e/nm²

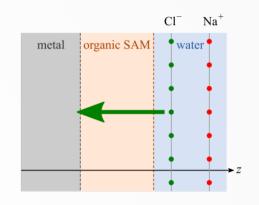
organic SAM-12 water

2.4

metal







SAM-x = SAM composed of CA-x(CA = carboxylic acid)

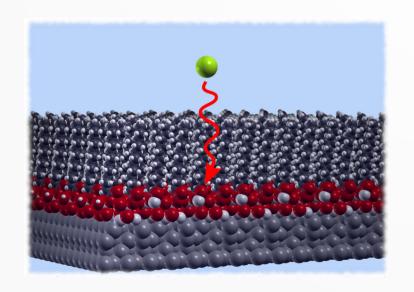
SAM needs some thickness for solvation barrier to fully develop!

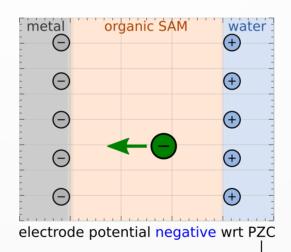
Penetration of a single Cl-

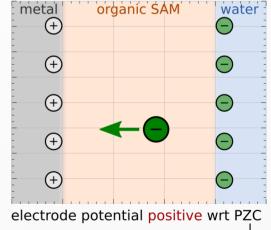


... as a function of electrode potential

(simple Helmholtz double-layer picture)



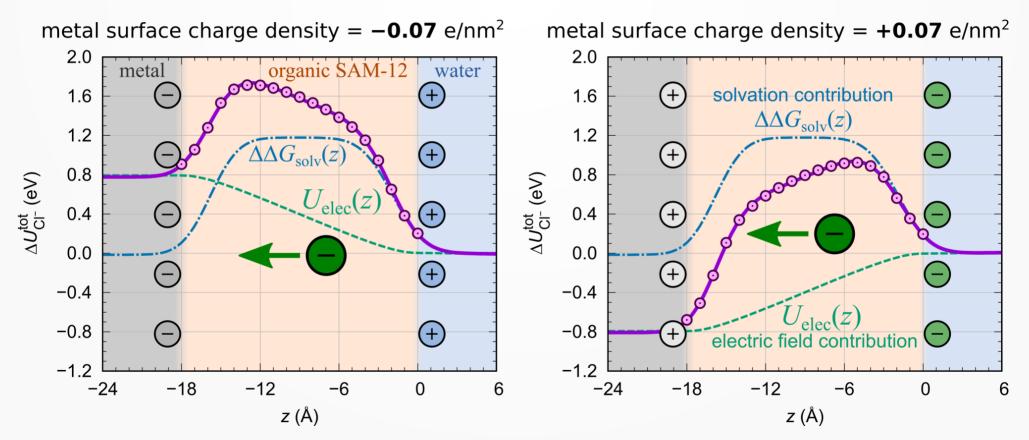




→Potential of Zero Charge

Penetration of a single Cl-

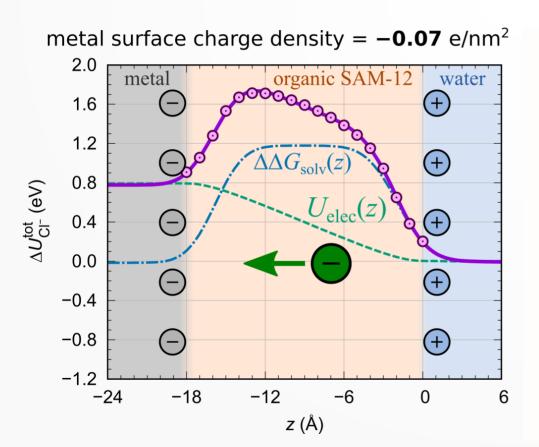


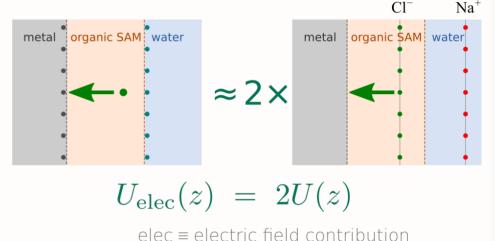


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Penetration of a single Cl-



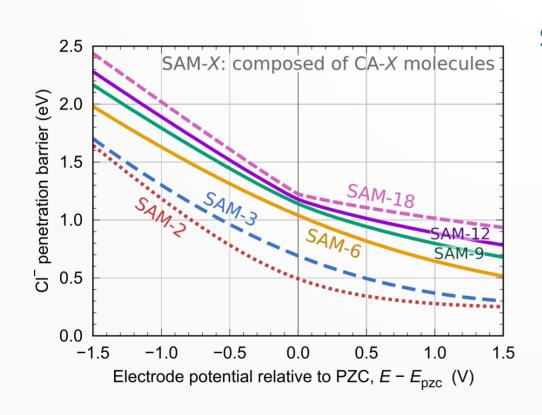




Note also: electrode potential is associated with $U_{
m elec}(z)$



CI penetration vs. electrode potential

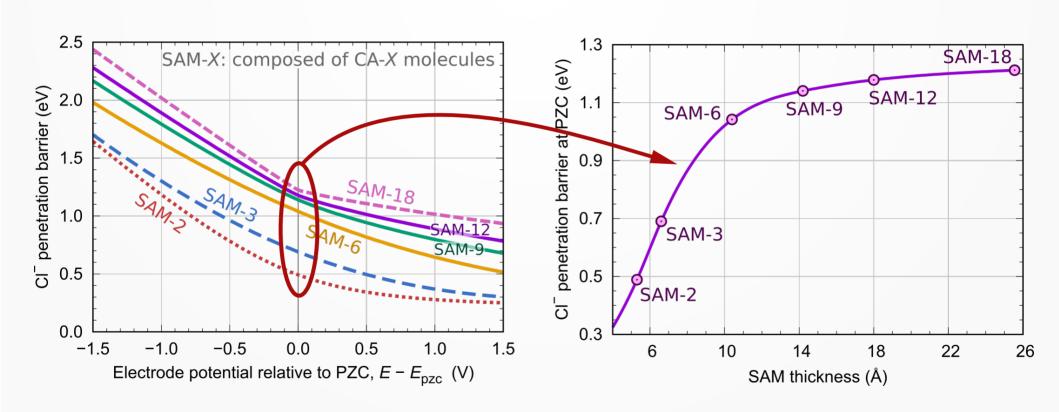


Simplifying assumptions:

- CA molecules fully cover the surface irrespective of the alkyl chain length (in reality only long-chain CAs form a complete SAM)
- surface is fully covered by SAM at all electrode potentials
- elastic penalty for Cl⁻ penetration is neglected
- •



CI penetration vs. electrode potential



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Conclusions



- The mechanism by which SAM hinders the penetration of Cl⁻ ions into SAM understood with aid of a simple model
- Contributions to penetration barrier:
 - inferior solvation of ions in SAM ($\triangle \Delta G_{solv}$)
 - contribution due to electric field in the Helmholtz double-layer (U_{elec})
 - elastic penalty (currently neglected)
- SAM needs to be thicker than about 10 Å for barrier to fully develop
- Developed model is based on electrostatic arguments and is thus generally applicable (can treat the penetration of any ions, including the dissolution of metals)

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Dept. Physical & Organic Chemistry, Jožef Stefan Institute, Slovenia











Thank you for your attention



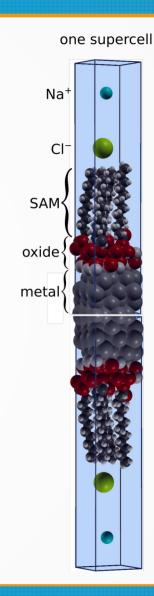
D. Costa

P. Marcus

F. Chiter

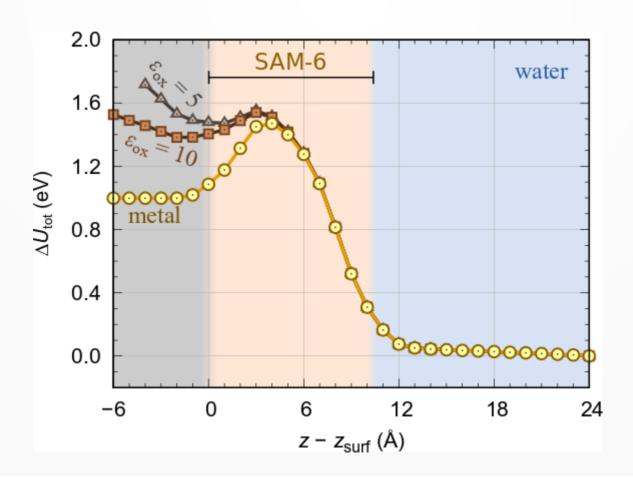
How to get rid of 3D PBC artifacts

simple but computationally inefficient method is to use symmetric setup



Oxide/SAM/water





Oxide/SAM/water



